

current to the anode and having a thickness of equal to or more than 100 μm and equal to or less than 500 μm ; and

a high voltage power source supplying a high frequency current between the anode and the cathode;

wherein said high frequency current includes frequencies which are more than 1 MHz, and said return plate is thicker than an entering depth of the high frequency current and restrainable from vibrating the return plate due to the laser gas flow.

2. (Amended) A laser apparatus comprising:

a laser chamber sealing a laser gas;

discharge electrodes constituted by a pair of anode and cathode provided within the laser chamber in an opposing manner, generating a discharge so as to excite a laser gas flowing therebetween and oscillating a laser beam;

a conductive anode base holding the anode;

an insulative cathode base holding the cathode;

a return plate electrically connecting the anode base to said laser chamber so as to supply a current to the anode; and

a high voltage power source supplying a high frequency current between the anode and the cathode;

wherein said high frequency current includes frequencies which are more than 1 MHz, and said return plate is thicker than an entering depth of the high frequency current and restrainable from

vibrating the return plate due to the laser gas flow;

wherein a thickness of the return plate is set to be equal to or more than 100 μm and equal to or less than 500 μm , and the return plate is arranged substantially in parallel to the laser gas flow between said discharge electrodes.

Ad
end